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projection aligner including at least one unit having a
surface on at least a portion of which a titanium oxide film
is provided [projecting and exposing a wafer with a pattern
on a reticle after said reticle is aligned with said wafer
using a projection aligner according to any one of claims 23
to 33]; and

developing the [said] wafer.

REMARKS

Applicants request favorable consideration and
allowance of the subject application.


Claims 1 through 34 are presented for
consideration, with Claims 1 through 3, 11 through 13, 22
through 25, and 34 being independent.

To place the subject application in better form,
the specification and Claims 1 through 4, 9 through 14, 19
through 26, and 31 through 34 have been amended to correct
minor informalities and to clarify features of the subject
invention. Also, a new abstract is presented in accordance
with preferred practice. No new matter has been added by
these changes.

Applicants submit that the instant application is in condition for allowance. Favorable consideration and an early Notice of Allowance are requested.

Applicants' undersigned attorney may be reached in our Washington, D.C. office by telephone at (202) 530-1010. All correspondence should be directed to our below-listed address.

Respectfully submitted,



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